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(71) Applicant: HOECHST JAPAN LIMITED
10-16, 8-chome, Akasaka, Minato-ku
Tokyo (JP)

(72) Inventor: Przybilla, Klaus Jürgen
Baustrasse 8

D-60322 Frankfurt (DE)

Inventor: Dammel, Ralph
8 Quimby Lane

Flemington, NJ 08822 (US)

Inventor: Pawłowski, Georg
Fritz-Kalle-Strasse 34

D-65187 Wiesbaden (DE)

Inventor: Kudo, Takanori Hoechst Japan
Limited

Advanced Technology Lab.,
3-2, Minamidai 1-chome

Kawagoe, Saitama (JP)

Inventor: Masuda, Seiya, Hoechst Japan
Limited

Advanced Technology Lab.,
3-2, Minamidai 1-chome

Kawagoe, Saitama (JP)

Inventor: Kinoshita, Yoshiaki, Hoechst Japan
Limited

Advanced Technology Lab.,

3-2, Minamidai 1-chome

Kawagoe, Saitama (JP)

Inventor: Suehiro, Natsumi, Hoechst Japan
Limited

Advanced Technology Lab.,

3-2, Minamidai 1-chome

Kawagoe, Saitama (JP)

Inventor: Padmanaban, Munirathna, Hoechst
Japan Limited

Advanced Technology Lab.,

3-2, Minamidai 1-chome

Kawagoe, Saitama (JP)

Inventor: Okazaki, Hiroshi, Hoechst Japan
Limited

Advanced Technology Lab.,

3-2, Minamidai 1-chome

Kawagoe, Saitama (JP)

Inventor: Endo, Hajime, Hoechst Japan
Limited

Advanced Technology Lab.,

3-2 Minamidai 1-chome

Kawagoe, Saitama (JP)

(74) Representative: WILHELM, KILIAN &

PARTNER Patentanwälte

Eduard-Schmid-Strasse 2

D-81541 München (DE)

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(54) Positive-working radiation-sensitive mixture.

(57) A novel positive-working radiation-sensitive mixture having a high sensitivity to radiation in a short-wavelength UV region is provided which can be developed in an aqueous alkaline solution, has a stable acid latent image and is used for the production of a semiconductor. The mixture comprises, as indispensable components, a) a binder insoluble in water but soluble in an aqueous alkaline solution, b) a compound having at least one bond cleavable with an acid, c) a compound capable of producing an acid upon radiation, and d₁) a basic ammonium compound or d₂) a basic sulfonium compound.